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(71)Applicant : RICOH CO LTD

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(72)Inventor : TATEWAKI TADAFUMI

FURUYA HIROMI

KAWAMURA FUMIO

(54) METHOD FOR MANUFACTURING REVERSIBLY THERMALLY RECORDING MEDIUM

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for manufacturing a reversibly thermally recording medium without appearing a skin fog by an erasing device such as an erasing bar or a thermal head, and to further provide a reversibly thermally recording medium capable of being rapidly erased and having good durability without notch on the medium.

SOLUTION: A reversely thermally recording medium has a reversibly thermally recording layer containing a reversibly heat sensitive composition, includes an electron donative colorational compound, an electron acceptive compound and a third component on at least a support, and is capable of forming a relatively color developing state due to a difference of a heating temperature and/or cooling speed after heating. A drying temperature when the layer is manufactured is a melting point or higher of the third component contained in the layer and melting points or lower of the electron donative colorational and acceptive compounds.

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